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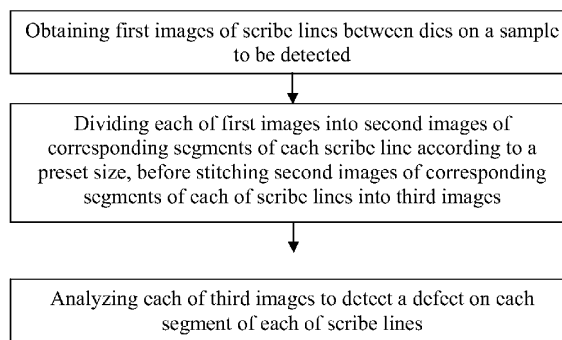
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(54) Title: SCRIBE LINE DEFECT DETECTION METHOD AND DETECTION SYSTEM, AND STORAGE MEDIUM

[Fig. 10]



(57) Abstract: A scribe line defect detection method, a scribe line defect detection system and a computer readable storage medium are provided. The scribe line defect detection method comprises the following steps: acquiring a first image of a plurality of scribe lines among a plurality of dies on a sample to be detected; segmenting each first image into second images of a plurality of scribe line segments according to a preset size, and stitching the second images of the scribe line segments corresponding to the scribe lines into a plurality of third images; and each third image is analyzed, so that defects on each scribe line segment of each scribe line can be detected respectively. By reconstructing the scribe line image with a large length-width ratio, the method can effectively avoid the damage of image scaling to fine defect features, thereby improving the detection rate of scribe line defects in the image.

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